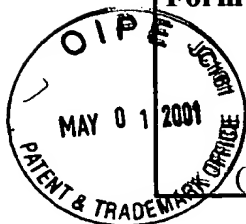


<b>Form 1449 (Modified)</b>  <b>Information Disclosure Statement By Applicant</b>  (Use Several Sheets if Necessary)	Atty Docket No.	Application No.:
	LAM1P157/P0718	09/746,900
Applicant:		
ANNAPRAGADA et al.		
Filing Date	Group	
12/22/00	2812	



### U.S. Patent Documents

Examiner Initial	No.	Patent No.	Date	Patentee	Class	Sub-class	Filing Date
	A						
	B						
	C						
	D						
	E						
	F						
	G						
	H						
	I						

### Foreign Patent or Published Foreign Patent Application

Examiner Initial	No.	Document No.	Publication Date	Country or Patent Office	Class	Sub-class	Translation	
							Yes	No
	J							
	K							
	L							
	M							
	N							

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### Other Documents

Examiner Initial	No.	Author, Title, Date, Place (e.g. Journal) of Publication
<i>amc</i>	O	U.S. Patent Application No. 09/746,901, Entitled "Method of Preventing Damage to Organo-Silicate Glass Materials during Resist Stripping", Filed 12/22/00, Inventor(s): Annapragada
<i>amc</i>	P	U.S. Patent Application No. 09/746,894, Entitled "Combined Resist Strip and Barrier Etch Process for Dual Damascene Structures", Filed 12/22/00, Inventor(s): Annapragada et al.
	Q	
Examiner <i>A. Michelle Gowell</i>		Date Considered <i>10-07-02</i>

**TC 1700**

Examiner: Initial citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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